

Controlled Environment Chuck®

MODEL # EX-1

Expand your process window with the NovaCentrix Controlled Environment Chuck EX-1. Designed for use with any PF 1000 series tool, the EX-1 allows sample processing beyond standard atmospheric conditions. Pre-heat samples up to 300°C or increase thermal transfer by cooling. A porous vacuum chuck minimizes thermal contact resistance and supports simple, repeatable sample placement. The EX-1 sealed chamber allows purging with N₂ or any other process gas. An external vacuum pump option is also available taking photonic curing into a vacuum environment. Take R&D to the next level with the NovaCentrix EX-1.

FEATURES

- Straightforward sample processing/alignment on porous vacuum chuck surface
- User-selectable controlled temperature range from 10°C to 300°C
- Removable hinged chamber lid with quartz window allows vacuum and pressurized processes
- Vacuum to 200mT and below with external vacuum pump option
- Designed for operation on existing PF 1000 series sample table
- Integrated bolometer holder for quick process checks

CHUCK CONFIGURATIONS

1. Base Controlled Environment Chuck
 - Temperature-controlled (10°- 300°) vacuum surface
 2. Base Controlled Environment Chuck with Sealed Chamber*
 - Temperature-controlled (10°- 300°) vacuum surface
 - Pressurized or vacuum processing capability (with user-supplied vacuum pump)
 3. Base Controlled Environment Chuck, Sealed Chamber*, and External Vacuum Pump
 - Temperature-controlled (10°- 300°) vacuum surface
 - Pressurized or vacuum processing (below 200 mT)
- * Sealed Chamber available with two quartz window options based on expected use of the PulseForge:
- Fused Quartz - Suitable for PulseForge operation up to 500V
 - Synthetic Fused Silica - For processing above 500V, fused silica preferred due to high UV transmittance

